

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Akira IKUSHIMA, Kazuya SAITO, Takashi MIURA  
and Shogo NASUDA  
For : METHOD OF PROCESSING A SILICA GLASS  
FIBER  
Group Art Unit : 1731  
Examiner : John Hoffmann  
Docket : ADACHI P163USP2



#4  
JH  
8-16-01

The Commissioner of Patents and Trademarks  
Washington, D.C. 20231

**INFORMATION DISCLOSURE STATEMENT**

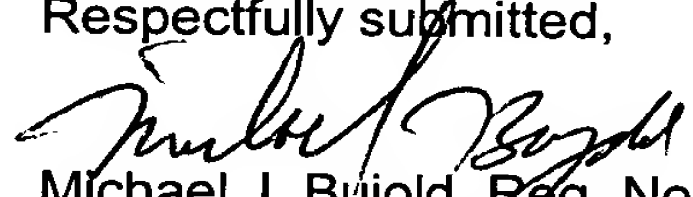
Dear Sir:

In connection with this matter, the Applicant hereby attaches one (1) United States Patent Office Form PTO-1449 and copies of the information listed in the enclosed PTO-1449 Form, unless otherwise indicated on such Form.

Copies of the information being made of record in this Information Disclosure Statement is not being submitted, as permitted by 37 CFR 1.98(d), as this information was previously cited by or submitted to the United States Patent and Trademark Office in a prior application, namely United States Patent Application Serial No. 09/351,951 filed July 12, 1999 and that prior application is properly identified in this statement and relied upon for an earlier filing date under 35 USC 120.

In the event that there are any fee deficiencies or additional fees are payable, please charge the same or credit any overpayment to our Deposit Account (Account No. 04-0213).

Respectfully submitted,

  
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## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Sub-Class	Filing Date, if Appropriate
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	4,157,253	Jun. 1979	Hernquist		
	4,182,664	Jan. 1980	Maklad		
	5,267,343	Nov. 1993	Lyons		
	5,620,496	Apr. 1997	Erdogan		
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	6,058,739	May 2000	Morton		
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## FOREIGN PATENT DOCUMENTS

Examiner Initials	Document Number	Date	Country	Sub-Class	Class	Translation Yes	No
	0 687 924 A1	Dec. 20, 1995	EPO				
	2808457	Aug. 1974	Germany				
	4-342427		Japan				
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	6-199539	Jun. 7, 1994	Japan				
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"Thermal Annealing of Defects Induced by ArF Excimer Laser Irradiation in a SiO<sub>2</sub>"; Japanese Society of Applied Physics, Catalog No. AP 90110-02 (English Translation)

ROTHSCHILD, Mordechai, Daniel J. EHRLICH and David C. SHAVER, "Eximer Laser Induced Damage in Fused Silica", *Microelectronic Engineering* 11, 1990, pp. 167-172.

"Temperature Dependence of the E<sup>1</sup> Center Creation in Silica Glasses", *Physica Status Solidi (b)*, vol. 147, No. 1, 1988, pp.k1-k4.

